

Title (en)  
POLISHING PAD AND METHOD FOR MANUFACTURING SAME

Title (de)  
POLIERKISSEN UND VERFAHREN ZUR HERSTELLUNG DAVON

Title (fr)  
TAMPON À POLIR ET SON PROCÉDÉ DE FABRICATION

Publication  
**EP 2853350 A4 20160113 (EN)**

Application  
**EP 13793745 A 20130212**

Priority  
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• KR 2013001085 W 20130212

Abstract (en)  
[origin: EP2853350A1] Polishing pad and method of manufacturing the same, the method, whereby materials for forming a polishing layer are mixed and solidified by a chemical reaction so as to manufacture the polishing pad, the method including: grinding organic materials by using a physical method so as to form micro-organic particles; mixing the micro-organic particles formed in the operation with the materials for forming the polishing layer; mixing at least one selected from the group consisting of inert gas, a capsule type foaming agent, and a chemical foaming agent that are capable of controlling sizes of pores, with the mixture in the operation so as to form gaseous pores; performing gelling and hardening of the mixture generated in the operation so as to form a polishing layer; and processing the polishing layer so as to distribute open pores defined by opening gaseous pores on a surface of the polishing layer.

IPC 8 full level  
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Citation (search report)  
• [XY] US 2003220061 A1 20031127 - PRASAD ABANESHWAR [US]  
• [Y] WO 2010053729 A1 20100514 - GUISELIN OLIVIER L [US]  
• [Y] WO 2004076127 A1 20040910 - DOW GLOBAL TECHNOLOGIES INC [US], et al  
• [A] EP 1357161 A2 20031029 - JSR CORP [JP]  
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Citation (examination)  
• EP 1201368 A2 20020502 - JSR CORP [JP]  
• EP 1175965 A2 20020130 - EBARA CORP [JP]  
• See also references of WO 2013176378A1

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DOCDB simple family (publication)  
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